

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Chunyuan ("Luis") Chao et al
Assignee: Mosel-Vitellic, Inc.
Title: Dynamically Controllable Reduction of Vertical Contact Diameter
Through Adjustment of Etch Mask Stack for Dielectric Etch
Application No.: 10/718,320 Filing Date: 11/19/2003
Examiner: Deo, Duy Vu Nguyen Group Art Unit: 1765
Docket No.: M-15208-US Confirm No.: 1058

San Jose, California
October 19, 2006

MailStop: RCE

**COMMISSIONER FOR PATENTS
P.O. BOX 1450
ALEXANDRIA, VA 22313-1450**

REQUEST FOR CONTINUED EXAMINATION (RCE)

AND AMENDMENT

Dear Sir:

In response to the Office Action having a mailing date of May 19, 2006, please amend the application as set forth below.

Continued examination (RCE) is requested pursuant to 37 CFR §1.114.

A two months extension of time is requested.

A Rule 132 Declaration accompanies this submission.

Claims Listing begins on page 2 of this paper.

Remarks begin on page 9 of this paper.

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